

L Number	Hits	Search Text	DB	Time stamp
1	213	anneal\$5 near10 laser near10 ion near2 beam	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/27 10:58
2	11	anneal\$5 near10 laser near10 ion near2 beam near5 (ar or argon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/27 14:23
3	290	(shin near2 hashimoto or takenobu near2 kishida or kyoko near2 egashira or yoshifumi near2 hata or toru near2 nishiwaki or tomoya near2 tanaka).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/27 14:25
4	3	((shin near2 hashimoto or takenobu near2 kishida or kyoko near2 egashira or yoshifumi near2 hata or toru near2 nishiwaki or tomoya near2 tanaka).in.) and (cobalt near2 (disilicide or silicide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/27 14:43
5	4	("4861750" "4992298").pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/27 14:43
-	0	nuetron near4 beam near15 particle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 11:05
-	421	neutron near4 beam near15 particle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 11:06
-	3	neutron near4 beam near15 particle near10 (ar or argon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 11:05
-	58	neutron near4 beam near15 particle near10 ion	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 11:15
-	5	neutron near4 beam near15 particle same lattice near2 defect	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 11:46
-	236	(shin near2 hashimoto or takenobu near2 kishida or kyoko near2 egashira or toru near2 nishiwaki or tomoya near2 tanaka).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 11:47
-	15	((shin near2 hashimoto or takenobu near2 kishida or kyoko near2 egashira or toru near2 nishiwaki or tomoya near2 tanaka).in.) and silicide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 11:49
-	2	4479829.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 11:49

-	1393	("cosi.sub.2" or (cobalt adj (disilicide or silicide))) same (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 16:23
-	412	("cosi.sub.2" or (cobalt adj (disilicide or silicide))) same (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) same (si or silicon) near3 (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 16:23
-	116	("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 16:36
-	2	4724223.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 16:33
-	98	("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) same (co or cobalt) near2 (film or layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 16:36
-	73	("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) same (co or cobalt) near (film or layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 16:44
-	0	("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) near5 insulat\$5 same (co or cobalt) near (film or layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 16:44
-	0	("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) near5 n\$1type same (co or cobalt) near (film or layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 16:44
-	4	("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6) near15 (si or silicon) near3 (substrate or wafer) near5 dop\$5 same (co or cobalt) near (film or layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 16:49
-	416	("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (si or silicon) near3 (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 16:50
-	16	("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (si or silicon) near3 (substrate or wafer) near5 (insulat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 17:49
-	46	epitax\$7 near10 ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (si or silicon) near3 (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 17:49
-	19	epitax\$7 near10 ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) near15 (si or silicon) near3 (substrate or wafer) same (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal\$6)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/25 18:04

-	31	epitax\$7 near10 ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) same (si or silicon) near3 (substrate or wafer) same (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 13:32
-	2	"20020076882"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 10:25
-	4	epitax\$7 near10 ("cosi.sub.2" or (cobalt adj (disilicide or silicide))) same (si or silicon) near3 (substrate or wafer) same (anneal\$5 or heat near2 treat\$5 or rta or rtp or rapid near2 thermal) and mosfet	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 13:33
-	373	(silicon near2 (oxide or dioxide) or (sio or "sio.sub.2")) same (argon or ar) near5 beam	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 14:47
-	3	(silicon near2 (oxide or dioxide) or (sio or "sio.sub.2")) same (argon or ar) near5 beam same oxygen near5 atoms	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 14:47
-	52	(silicon near2 (oxide or dioxide) or (sio or "sio.sub.2")) near10 (argon or ar) near5 beam	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 14:54
-	36	(oxygen or "o.sub.2") near10 (implant\$5 or concentrat\$5) same (cobalt near2 (silicide or disilicide) or "cosi.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 14:55